10

nm or more,

ABSTRACT

The present invention provides a negative photosensitive resin composition comprising (A) a

- photocurable resin having a photosensitive group or groups crosslinkable by light irradiation, (B) a photoacid generator and (C) a photosensitizer which is a benzopyran condensed ring compound capable of increasing photosensitivity to visible light with a wavelength of 480
- a negative photosensitive dry film prepared by applying the photosensitive resin composition to a surface of support film, followed by drying, to form a photosensitive resin layer, and
- 15 a method of forming a pattern using the resin composition or the dry film.